Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"6319635".pn. or "6011646".pn.	US-PGPUB; USPAT	OR	ON	2005/02/09 09:46
L2	4	"6489066".pn. or "6110607".pn. or "6319635".pn. or "5698113".pn.	US-PGPUB; USPAT	OR	ON	2005/02/09 09:52
L3	2	(Mirkarimi.in. or Spiller.in. or Stearns.in. or (Lawrence adj Livermore).as. or (Department near2 Energy).as. or (euv).as. or (euvllc).as.) and ((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (Si or silicon or euv or reticle or mirror or amorphous or only))	US-PGPUB; USPAT	OR	ON	2005/02/09 10:33
L4	1	(Mirkarimi.in. or Spiller.in. or Stearns.in. or (Lawrence adj Livermore).as. or (Department near2 Energy).as. or (euv).as. or (euvllc).as.) and ((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (Si or silicon or euv or reticle or mirror or amorphous or only))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 10:02
L5	1416	(427/533,534,551,595).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:03
L6	628	(427/585).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:03
L7	665	(427/160).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:03
L8	1648	(427/162,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:03
L9	2689	(427/248.1,255.7).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:03
L10	599	(427/331).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:03
L11	405	(204/192.11).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:04
L12	1188	(204/192.32,192.34).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:04
L13	229	(204/192.37).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:04
L14	1384	(359/584,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:04
L15	3892	(428/446,450).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/02/09 10:05

L16	13562	L5 L6 L7 L8 L9 L10 L11 L12 L13 L14 L15	US-PGPUB; USPAT	OR	ON	2005/02/09 10:13
L17	56	L11 and L12	US-PGPUB; USPAT	OR	ON	2005/02/09 10:10
L18	3	L11 and L13	US-PGPUB; USPAT	OR	ON	2005/02/09 10:05
L19	7	(L11 or L12 or L13) and (L14 or L15)	US-PGPUB; USPAT	OR	ON	2005/02/09 10:11
L20	22	(L11 or L12 or L13) and (L7 or L8)	US-PGPUB; USPAT	OR	ON	2005/02/09 10:11
L21	28	(L5 L6 L7 L9 L10 L11 L12 L13) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4))	US-PGPUB; USPAT	OR	ON	2005/02/09 10:15
L22	28	(L5 L6 L7 L9 L10 L11 L12 L13) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4))	US-PGPUB; USPAT	OR	ON	2005/02/09 10:16
L23	29	(L5 L6 L7 L9 L10 L11 L12 L13) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	US-PGPUB; USPAT	OR	ON	2005/02/09 10:23
L24	28	(L8 or L14 or L15) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	US-PGPUB; USPAT	OR	ON	2005/02/09 10:34
L25	23	L24 not L23	US-PGPUB; USPAT	OR	ON	2005/02/09 10:23
L26	42	L16 and ((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (Si or silicon or euv or reticle or mirror or amorphous or only))	US-PGPUB; USPAT	OR	ON	2005/02/09 11:00

L27	7	L26 and ((((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	US-PGPUB; USPAT	OR	ON	2005/02/09 13:09
L28	35	L26 not L27	US-PGPUB; USPAT	OR	ON	2005/02/09 10:40
L29	27	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (Si or silicon or euv or reticle or mirror or amorphous or only)) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	US-PGPUB; USPAT	OR	ON	2005/02/09 10:53
L30	20	L29 not L27	US-PGPUB; USPAT	OR	ON	2005/02/09 10:46
L31	1	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (Si or silicon or euv or reticle or mirror or amorphous or only)) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 10:54
L32	2	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray))) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 10:54

L33	17	((planariz$6 or polish$4 or smooth$4 or mill$4) with (Si or silicon or euv or reticle or mirror or amorphous or only)) and (((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 10:55
L34	16	L33 not L32	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 10:55
L35	0	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (only near3 (silicon or Si or amorphous)))	US-PGPUB; USPAT	OR	ON	2005/02/09 11:01
L36	3	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (only with (silicon or Si or amorphous)))	US-PGPUB; USPAT	OR	ON	2005/02/09 11:03
L37	0	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (only with (silicon or Si or amorphous)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 11:03
L38	1	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (amorphous with (silicon or Si)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 11:04
L39	7	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with (amorphous with (silicon or Si)))	US-PGPUB; USPAT	OR	ON	2005/02/09 11:05
L40	5	L39 not L36	US-PGPUB; USPAT	OR	ON	2005/02/09 11:04
L41	152	((planariz$6 or polish$4 or smooth$4 or mill$4) with (ion near2 (gun or beam or ray)) with ((silicon or Si)))	US-PGPUB; USPAT	OR	ON	2005/02/09 11:11
L42	20	L41 and L16	US-PGPUB; USPAT	OR	ON	2005/02/09 11:06
L43	132	L41 not L42	US-PGPUB; USPAT	OR	ON	2005/02/09 11:09
L44	63	((planariz$6 or polish$4 or smooth$4) with (ion near2 (gun or beam or ray)) with ((silicon or Si)))	US-PGPUB; USPAT	OR	ON	2005/02/09 11:16
L45	48	L44 not L42	US-PGPUB; USPAT	OR	ON	2005/02/09 11:12

L46	17	((planariz$6 or polish$4 or smooth$4) with (ion near2 (gun or beam or ray)) with ((silicon or Si)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 11:19
L47	4	((planariz$6 or polish$4 or smooth$4) with (ion near2 (gun or beam or ray)) with ((amorphous)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 11:20
L48	23	((planariz$6 or polish$4 or smooth$4) with (ion near2 (gun or beam or ray)) with ((amorphous)))	US-PGPUB; USPAT	OR	ON	2005/02/09 12:08
L49	34	(refract$4 adj index) with (amorphous adj carbon)	US-PGPUB; USPAT	OR	ON	2005/02/09 12:18
L50	2053	(refract$4 adj index) with (TiO2 or ("TiO.sub.2"))	US-PGPUB; USPAT	OR	ON	2005/02/09 12:13
L51	218	L50 and L16	US-PGPUB; USPAT	OR	ON	2005/02/09 12:13
L52	16	(amorphous adj carbon) same ((ion adj beam adj sputter$3 adj deposit$4) or IBSD)	US-PGPUB; USPAT	OR	ON	2005/02/09 12:22
L53	1	(amorphous adj carbon) same ((ion adj beam adj sputter$3 adj deposit$4) or IBSD)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 12:22
L54	9	(amorphous adj carbon) same ((ion adj beam adj sputter$3 adj deposit$4) or IBSD) and ((Ar or argon or Kr or krypton or xe or xenon or Ne or neon) with (ion or beam))	US-PGPUB; USPAT	OR	ON	2005/02/09 12:23
L55	21	(((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon)))) and (ion with normal)	US-PGPUB; USPAT	OR	ON	2005/02/09 13:30
L56	22	((ion adj beam adj sputter$4) with deposit$4 with (si or silicon)) same (energy or ev)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/02/09 13:23
L57	154	(((extreme adj (uv or ultraviolet or (ultra adj violet))) or euv or (e adj uv)) near3 (lithograph$6 or photolithograph$6 or mask or reticle or mirror or reflect$4 or multilayer or (multi adj layer) or ((Mo or molybdenum) near2 (Si or silicon)))) and ((Si or silicon) near2 (Be or beryllium))	US-PGPUB; USPAT	OR	ON	2005/02/09 13:31
L58	14	L57 and L16	US-PGPUB; USPAT	OR	ON	2005/02/09 13:31